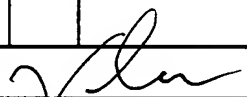


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OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)			
LV		Songlin Xu et al., "Wall-dependent etching characteristics of organic antireflection coating in O ₂ +halogen/hydrogen halide plasma", J.Vac Sci. Technol. A 19(6), Nov/Dec 2001	
LV		Songlin Xu et al., "Gate Oxide Integrity Issue Cause by Wall-Related Process Drivt in Plasma Etching", 2002 7 th International Symposium on Plasma-and Process-Induced Damage June 6-7, Maui HI, USA	
LV		Songlin Xu et al., "Characteristics and mechanism of etch process sensitivity to chamber surface condition", J. Vac. Sci. Technol. B19(1), Jan/Feb 2001	
Examiner Signature		Date Considered	4/11/05

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